What is Claimed is:

1. A liquid crystal display including a first substrate having an active layer with source/drain regions formed therein, and a gate line and a data line formed thereon extending in directions perpendicular to each other, the liquid crystal display comprising:

a dummy gate insulating film and a dummy gate electrode both formed on the first substrate in fixed patterns isolated from the gate line;

an interlayer insulating film on the first substrate inclusive of the dummy gate electrode,

a drain electrode formed on the interlayer insulating film so as to be in contact with the drain region, to have a step to the data line, and to overlap a portion of the dummy gate electrode;

a passivation film formed on the interlayer insulating film inclusive of the dummy gate electrode and the data line;

a contact hole formed to expose the drain electrode overlapping the dummy gate electrode; and,

a pixel electrode overlapping upper edges of the data line and in contact with the drain electrode through the contact hole.

2. A liquid crystal display as claimed in claim 1, wherein a position of the drain electrode where the contact hole is formed is higher than a position where the data line is formed.

3. A liquid crystal display as claimed in claim 1, wherein a first thickness of the passivation film over the drain electrode where the contact hole is formed is less than a second

thickness of the passivation film over the data line.

4. A liquid crystal display as claimed in claim 1, further comprising a source electrode projected from the data line to be in contact with the source region.

5. A liquid crystal display including a first substrate having an active layer with source/drain regions formed therein, and a gate line and a data line formed thereon extending in directions perpendicular to each other, the liquid crystal display comprising:

a dummy gate insulating film and a dummy gate electrode both formed on the first substrate in fixed patterns isolated from the gate line;

an interlayer insulating film on the first substrate inclusive of the dummy gate electrode and exposing a part of the first substrate where the data line is formed;

a drain electrode formed on the interlayer insulating film electrode so as to be in contact with the drain region, to have a step to the data line, and to overlap a portion of the dummy gate;

a passivation film formed on the interlayer insulating film inclusive of the dummy gate electrode and the data line;

a contact hole formed to expose the drain electrode overlapping the dummy gate electrode; and,

a pixel electrode overlapping upper edges of the data line and in contact with the drain electrode through the contact hole.

6. A liquid crystal display as claimed in claim 5, wherein a position of the drain electrode where the contact hole is formed is higher than a position where the data line is

formed.

7. A liquid crystal display as claimed in claim 5, wherein a first thickness of the passivation film over the drain electrode where the contact hole is formed is less than a second thickness of the passivation film over the data line.

8. A liquid crystal display as claimed in claim 5, further comprising a source electrode projected from the data line to be in contact with the source region.

9. A method for fabricating a liquid crystal display including a first substrate having an active layer with source/drain regions formed therein, and a gate line and a data line extending in directions perpendicular to each other formed thereon, the method comprising:

(a) forming the gate line at a same time while forming a dummy gate insulating film and a dummy gate electrode both on the first substrate in fixed patterns isolated from the gate line;

(b) forming an interlayer insulating film on the first substrate inclusive of the dummy gate electrode and the gate line so as to have a step;

(c) forming the data line at a same time while forming a drain electrode on the interlayer insulating film so as to be in contact with the drain region, to have a step to the data line, and to overlap a portion of the dummy gate electrode;

(d) forming a passivation film on the interlayer insulating film inclusive of the dummy gate electrode and the data line;

(e) forming a contact hole to expose the drain electrode overlapping with the dummy gate electrode; and,

(f) forming a pixel electrode on the passivation film to be overlapped on upper edges of the data line and in contact with the drain electrode through the contact hole.

10. A method as claimed in claim 9, wherein the dummy gate electrode has a width larger than a width of the drain electrode.

11. A method as claimed in claim 9, wherein the passivation film has a first thickness over the data line which is greater than a second thickness of the passivation film over the drain electrode where the contact hole is formed.

12. A method as claimed in claim 9, wherein the pixel electrode is formed of indium-tin-oxide (ITO).

13. A method as claimed in claim 9, wherein an upper surface of the passivation film is substantially flat.

14. A method for fabricating a liquid crystal display including a first substrate having an active layer with source/drain regions formed therein, and a gate line and a data line extending in directions perpendicular to each other formed thereon, the method comprising:

(a) forming the gate line at a same time while forming a dummy gate insulating film and a dummy gate electrode both on the first substrate in fixed patterns isolated from the gate line;

(b) forming an interlayer insulating film on the first substrate inclusive of the dummy gate electrode and the gate line to expose a portion of the first substrate where the data line is formed;

(c) forming the data line on the exposed portion of the first substrate at a same time while forming a drain electrode on the interlayer insulating film so as to be in contact with the drain region, to have a step to the data line, and to overlap a portion of the dummy gate electrode;

(d) forming a passivation film on the interlayer insulating film inclusive of the dummy gate electrode and the data line;

(e) forming a contact hole to expose the drain electrode overlapping the dummy gate electrode; and,

(f) forming a pixel electrode on the passivation film to be overlapped on upper edges of the data line and in contact with the drain electrode through the contact hole.

15. A method as claimed in claim 14, wherein the dummy gate electrode has a width larger than a width of the drain electrode.

16. A method as claimed in claim 14, wherein the passivation film has a first thickness over the data line which is greater than a second thickness of the passivation film over the drain electrode where the contact hole is formed.

17. A method as claimed in claim 14, wherein the pixel electrode is formed of indium-tin-oxide (ITO).

18. A method as claimed in claim 14, wherein an upper surface of the passivation film is substantially flat.

19. A method as claimed in claim 14, wherein a width of the exposed portion of the first substrate is greater than a width of the data line.

20. A liquid crystal display (LCD) device having a first substrate having an active layer with source/drain regions formed therein, the LCD device comprising:

a gate line formed on the substrate extending in a first direction;

a dummy gate electrode formed on the substrate;

a data line formed on the substrate extending in a second direction substantially perpendicular to the first direction;

a first insulating layer formed on the substrate and covering the gate line and the dummy gate electrode;

a drain electrode having a first portion connected to the drain region and a second portion extending above the dummy gate electrode;

a second insulating layer formed on the first insulating layer and covering the data line, the second insulating layer having a contact hole defined therein exposing the second portion of the drain electrode; and

a transparent conductive layer formed above the second insulating layer, overlapping at least a portion of the data line, and contacting the drain electrode through the contact hole defined in the second insulating layer.

21. The LCD device of claim 20, further comprising a dummy gate insulating film formed between the dummy gate electrode and the substrate.

22. The LCD device of claim 20, wherein the second portion of the drain electrode is located a greater distance above the substrate than the data line.

23. The LCD device of claim 20, wherein the data line is formed on the first insulating layer.

24. The LCD device of claim 20, wherein the first insulating layer includes a channel and wherein the data line is formed in the channel.

25. The LCD device of claim 24, wherein the channel exposes a portion of the substrate.

26. The LCD device of claim 20, wherein a first thickness of the second insulating layer over the second portion of the drain electrode where the contact hole is formed is less than a second thickness of the second insulating layer over the data line.

27. A method of fabricating a liquid crystal display (LCD) device including a first substrate having an active layer with source/drain regions formed therein, the LCD device comprising:

forming at a same time on the substrate a dummy gate electrode and a gate line extending in a first direction;

forming a first insulating layer formed on the substrate covering the gate line and the dummy gate electrode;

forming at a same time on the substrate a data line extending in a second direction substantially perpendicular to the first direction and a drain electrode having a first portion connected to the drain region and a second portion extending above the dummy gate electrode;

forming a second insulating layer on the first insulating layer covering the dummy gate electrode, the second insulating layer having a contact hole defined therein exposing the second portion of the drain electrode; and

forming a transparent conductive layer formed above the second insulating layer, overlapping at least a portion of the data line, and contacting the drain electrode through the contact hole defined in the second insulating layer.

28. The method of claim 27, further comprising forming a dummy gate insulating film prior to forming the dummy gate electrode and the gate line.

29. The method of claim 27, wherein the second portion of the drain electrode is formed a greater distance above the substrate than the data line.

30. The method of claim 27, wherein the data line is formed on the first insulating layer.

31. The method of claim 27, further comprising forming a channel in the first insulating layer prior to forming the data line, wherein the data line is formed in the channel.

32. The method of claim 27, wherein the channel exposes a portion of the substrate.